

## CORRECTION

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## Correction: Nano-spherical tip-based smoothing with minimal damage for 2D van der Waals heterostructures

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Correction for 'Nano-spherical tip-based smoothing with minimal damage for 2D van der Waals hetero-structures' by Xiaolei Ding *et al.*, *Nanoscale*, 2025, **17**, 3095–3104, <https://doi.org/10.1039/D4NR03583F>.

Dr Baoshi Qiao, one of the authors of this manuscript, was incorrectly named as Boshi Qiao in the original article.

The authors regret that a duplicated version of Fig. 4(a) and (e) was included in the originally published article. The correct version of Fig. 4 is shown here.

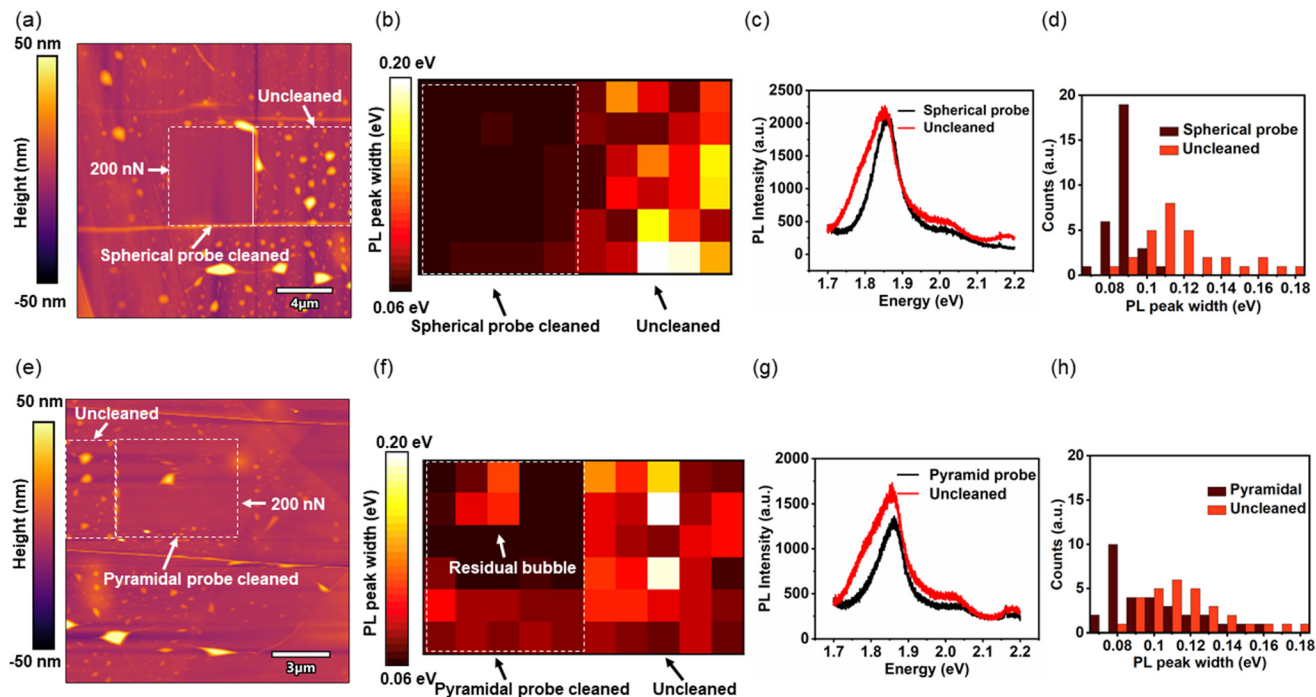
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**Fig. 4** (a) AFM topography of the nano-spherical probe-cleaned and uncleaned regions on the MoS<sub>2</sub>/hBN substrate. (b) PL FWHM mapping of the nano-spherical probe-cleaned region and the uncleaned region in (a). (c) Individual PL spectra of the nano-spherical probe-cleaned and uncleaned regions from (a). (d) The statistical distribution graph of PL FWHM from (b). This shows that the nano-spherical probe can reduce the PL FWHM of the MoS<sub>2</sub>/hBN substrate, effectively decreasing material contamination. (e) AFM topography of pyramidal probe-cleaned and uncleaned regions on the MoS<sub>2</sub>/hBN substrate. (f) PL FWHM mapping of the pyramidal probe-cleaned region and the uncleaned region in (e). (g) Individual PL spectra of the pyramidal probe-cleaned and uncleaned regions from (e). (h) The statistical distribution graph of PL FWHM from (f). Although the pyramidal probe also reduces the PL FWHM of the MoS<sub>2</sub>/hBN substrate, its cleaning performance is inferior to that of the nano-spherical probe due to residual bubbles.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

